

THIRD SUPPLEMENTAL PRELIMINARY
AMENDMENT
U.S. Appl. No. 09/662,181

86. The coated substrate of claim 85, wherein the crystallites have an average size
between 0.5 and 100 nm.

REMARKS

Claims 33-86 are pending in the present application.

New Claims 78-86 have been copied or substantially copied from issued U.S. Patent No. 6,326,079. A copy of the '079 Patent was submitted in the Information Disclosure Statement filed July 19, 2002. Applicant has copied claims from the '079 Patent within the one year date under 35 U.S.C. 135(b) in order to preserve the right to provoke an interference. A Rule 607 request for declaration of an interference will be filed, if necessary.

Applicant believes that an Office Action has not yet issued in the present application. However, if that is not the case, the present Third Supplemental Preliminary Amendment is not intended to be a response to any outstanding Office Action. Rather, Applicant reserves the right to respond to such an Office Action in a separate paper.

Exemplary support for new Claims 78-86 in the present specification is identified in the following table:

TABLE

New Claims 78-86	Exemplary Support in the Present Application (U.S. Application Serial No. 09/662,181)
78. A coated substrate which is a glass substrate provided on at least a portion of one of its faces with a coating	"flat glass substrate" (page 1; lines 8-10; "titanium oxide ... coating" (1; 8-10)

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<p>having photocatalytic properties, and</p> <p>comprising titanium oxide at least partly crystallized in the anatase form, and obtained by chemical vapor deposition followed by an annealing heat treatment.</p>	<p>“titanium oxide” (1; 8-10); “chemical vapor deposition process” (7:21); [t]he temperature range at the point of application for the coating is usually about 1100°-1320°F/590°-715°C” (30; 28-30); “corresponding metal tetrachloride” (8; 5)</p>
<p>79. The coated substrate according to claim 1, wherein the coating has a thickness up to 130 nm.</p>	<p>Examples 1-7 (1300 Å = 130 nm) (<i>see</i>, Table 1)</p>
<p>80. A coated substrate which is</p> <p>a glass substrate provided on at least a portion of one of its faces with a coating having photocatalytic properties, and comprising titanium oxide at least partly crystallized in the anatase form, and</p> <p>wherein at least one thin layer is located between said substrate and said coating.</p>	<p>“flat glass substrate” (page 1; lines 8-10;</p> <p>“titanium oxide” (1; 8-10); “chemical vapor deposition process” (7:21); [t]he temperature range at the point of application for the coating is usually about 1100°-1320°F/590°-715°C” (30; 28-30)</p> <p>“additional coatings may include silicon and silica” (12; 26-27); “the glass substrate was float glass which had been initially provided with silica coating” (16; 25-27); “the coatings comprise a layer of silicon 58, a layer of silica 60, then a titanium oxide coating 62 on top of the article” (22; 21-23)</p>
<p>81. A coated substrate which is</p> <p>a glass substrate provided on at least a portion of one of its faces, and contacting said portion, with a coating having photocatalytic properties, and comprising titanium oxide at least partly crystallized in the anatase form.</p>	<p>“flat glass substrate” (page 1; lines 8-10;</p> <p>“titanium oxide” (1; 8-10); “[t]he coating may be applied directly to a substrate or as a layer in a plurality of coatings on a substrate” (32; 7-9); “chemical vapor deposition process” (7:21); [t]he temperature range at the point of application for the coating is usually about 1100°-1320°F/590°-715°C” (30; 28-30)</p>
<p>82. A coated substrate which is</p>	<p>“flat glass substrate” (page 1; lines 8-10;</p>

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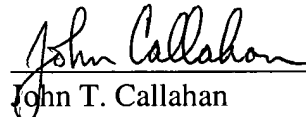
<p>a glass substrate provided on at least a portion of one of its faces, with a coating having photocatalytic properties, and comprising titanium oxide at least partly crystallized in the anatase form, and</p> <p>wherein an underlayer is present between, and contacts, said substrate and said coating, and which underlayer acts as a barrier with respect to alkali ions.</p>	<p>“titanium oxide” (1; 8-10); “chemical vapor deposition process” (7:21); [t]he temperature range at the point of application for the coating is usually about 1100°-1320°F/590°-715°C” (30; 28-30)</p> <p>“additional coatings may include silicon and silica” (12; 26-27); “the glass substrate was float glass which had been initially provided with silica coating” (16; 25-27); “the coatings comprise a layer of silicon 58, a layer of silica 60, then a titanium oxide coating 62 on top of the article” (22; 21-23)</p>
<p>83. A coated substrate which is</p> <p>a glass substrate provided on at least a portion of one of its faces, with a coating having photocatalytic properties, and comprising titanium oxide at least partly crystallized in the anatase form and an amorphous or partially crystalline oxide of titanium in other than anatase form.</p>	<p>“titanium oxide” (1; 8-10); “chemical vapor deposition process” (7:21); [t]he temperature range at the point of application for the coating is usually about 1100°-1320°F/590°-715°C” (30; 28-30); Examples 1-7</p>
<p>84. A double glass glazing comprising on at least a portion of one of its outer faces a coating having photocatalytic properties, wherein said coating comprises titanium oxide at least partly crystallized in the anatase form.</p>	<p>“architectural glazing” 911:7); “titanium oxide” (1; 8-10); “chemical vapor deposition process” (7:21); [t]he temperature range at the point of application for the coating is usually about 1100°-1320°F/590°-715°C” (30; 28-30)</p>
<p>85. A coated substrate which is</p> <p>a glass substrate provided on at least a portion of one of its faces with a coating having photocatalytic properties, and comprising titanium oxide at least partly crystallized in the anatase form,</p> <p>wherein the crystallized titanium oxide is in the form of crystallites, and the thickness of the coating is at least two times greater than the mean diameter of said crystallites.</p>	<p>“flat glass substrate” (page 1; lines 8-10;</p> <p>“titanium oxide” (1; 8-10); “chemical vapor deposition process” (7:21); [t]he temperature range at the point of application for the coating is usually about 1100°-1320°F/590°-715°C” (30; 28-30)</p> <p>Examples 1-7</p>

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86. The coated substrate of claim 85, wherein the crystallites have an average size between 0.5 and 100 nm	Examples 1-7
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Entry and consideration of the new claims is requested.

Respectfully submitted,



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APPENDIX

IN THE CLAIMS

Claims 78-86 have been added as new claims.